



09/614,113

Certificate

JUL 23 2007

of Correction

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventors: Pan et al.

Patent No.: 7,041,548 B1

Issued: May 9, 2006

For: METHODS OF FORMING A GATE
STACK THAT IS VOID OF SILICON
CLUSTERS WITHIN A METALLIC
SILICIDE FILM THEREOF

Attorney Docket No.: 2269-2915.3US

CERTIFICATE OF MAILING

I hereby certify that this correspondence along with any attachments referred to or identified as being attached or enclosed is being deposited with the United States Postal Service as First Class Mail on the date of deposit shown below with sufficient postage and in an envelope addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

July 10, 2007
Date

Signature

Joseph A. Walkowski
Name (Type/Print)

LETTER MAKING ERRORS OF RECORD

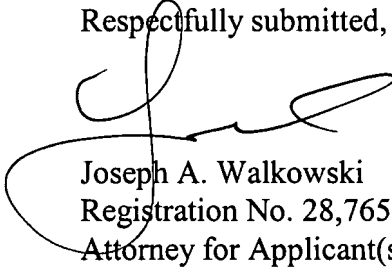
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Please make the following errors of record in the file history of the above-referenced Letters Patent:

COLUMN 1, LINE 28,	change “(“VSLI”)” to --(“VLSI”)--
COLUMN 1, LINE 29,	change “(“USLI”)” to --(“ULSI”)--
COLUMN 1, LINE 63,	change “such chemical” to --such as chemical--
COLUMN 3, LINE 45,	change “forming the” to --form the--
COLUMN 5, LINE 54,	change “clusters 116” to --clusters 116 (as shown in FIG. 10)--

Respectfully submitted,



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Document in ProLaw